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# AM-LCD 96

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THE JAPAN SOCIETY OF  
APPLIED PHYSICS



SOCIETY FOR INFORMATION DISPLAY

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JAPAN CHAPTER

## DIGEST OF TECHNICAL PAPERS

1996

INTERNATIONAL WORKSHOP ON  
ACTIVE-MATRIX  
LIQUID-CRYSTAL DISPLAYS  
in conjunction with IDW'96

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89

TOC

# CONTENTS

Nov. 27, Wednesday

## Opening Session (9:30-9:40)

- 9:30 Welcome Address  
S. Tanaka, *Univ. of Tokyo*

## Plenary (9:40-10:10)

- 9:40 Display Trends towards Multimedia Era  
M. Hosoya, *Sony, Japan*..... 1

## TFT1: poly-Si TFTs (10:25-12:45)

- 10:25 (TFT1-1) Low-Temperature poly-Si TFT-LCDs with Monolithic Drivers (Invited)  
M. Okabe, *Fujitsu Labs., Japan* ..... 5
- 10:50 (TFT1-2) Power Reduction of Driver-Integrated p-Si TFT-LCDs with Divided Shift-Registers  
Y. Kubota, Y. Yamane, Y. Ishii, S. Tsuchimoto, F. Funada and K. Awane, *Sharp, Japan*..... 9
- 11:10 (TFT1-3) Fabrication of poly-Si TFT at 450°C by Metal Induced Lateral Crystallization  
T-H. Ihn, B-I. Lee, K-H. Kim and S-K. Joo, *Seoul National Univ., Korea* ..... 13
- 11:30 (TFT1-4) Performance and Hot Carrier Reliability of NH<sub>3</sub> and N<sub>2</sub> Plasma Treated poly-Si TFTs  
H-Y. Lin, C-Y. Chang and T.F. Lei, *National Chiao Tung Univ., Taiwan* ..... 17
- 11:50 (TFT1-5) Film Thickness Effects in Laser Crystallised poly-Si TFTs  
S.D. Brotherton, D.J. McCulloch, J.P. Gowers, M. Trainor, M.J. Edwards and  
J.R. Ayres, *Philips Research Labs., U.K.* ..... 21
- 12:10 (TFT1-6) The Influence of the Contamination at the Low-Temperature poly-Si Crystallization on the TFT Characteristics  
T. Tanaka, T. Ohori, K. Oki and M. Okabe, *Fujitsu Labs., Japan* ..... 25
- 12:30 (TFT1-7) Low-Temperature poly-Si TFTs with a SiO<sub>2</sub>/TaO<sub>x</sub> Double Layered Gate Insulator and Al-Nd/Ti Gate Metal (Late-News)  
T. Yoshioka, S. Maegawa, H. Sano, M. Furuta, Y. Uraoka, H. Tsutsu,  
I. Kobayashi, T. Kawamura and Y. Miyata, *Matsushita Electric Industrial, Japan*... 389

## TFT2: a-Si TFT Technologies(14:00-16:20)

- 14:00 (TFT2-1) Copper-Gate Process for High Information Content a-Si TFT-LCDs (Invited)  
E.G. Colgan, P.M. Fryer, E. Galligan, W. Graham, R. Horton, D. Hunt,  
L. Jenkins, R. John, P. Koke, Y. Kuo, K. Latzko, F. Libsch, A. Lien, I. Lovas,  
R. Nywening, R. Polastre, M.E. Rothwell, J. Wilson, R. Wisnieff and S.L. Wright,  
*IBM, U.S.A.* ..... 29
- 14:25 (TFT2-2) TFT-LCDs with Selective Ta<sub>2</sub>O<sub>5</sub> Etching for Anodized Ta/TaN Gate Line  
M. Ikeda, M. Murooka and K. Suzuki, *Toshiba, Japan*..... 33
- 14:45 (TFT2-3) Electrical Performance and Instability of High Field-Effect Mobility a-Si:H TFTs Made from High Deposition-Rate PECVD Materials  
C-Y. Chen, C-S. Chiang, C. Malone\* and J. Kanicki, *Univ. of Michigan, U.S.A. and  
\*Optical Imaging System, U.S.A.* ..... 37
- 15:05 (TFT2-4) A Novel Vertical Offset Structure Thin-Film Transistor with High Performance  
C-W. Lin and C-Y. Chang, *National Chiao Tung Univ., Taiwan*..... 41
- 15:25 (TFT2-5) Effects of Back-Channel Etching on the Performance of a-Si:H Thin-Film Transistors  
M. Ando, M. Wakagi, T. Watanabe and T. Minemura, *Hitachi, Japan* ..... 45
- 15:45 (TFT2-6) TFD's for High Quality AMLCD on Low Temperature Plastics  
J.M. Shannon, S-M. Chen, G. Oversluizen\*, R.A.C.M.M. van Swaaij, A.D. Annis  
and B.J. Sealy, *Univ. of Surrey, U.K. and \*Philips Research Labs., Netherlands*..... 49
- 16:05 (TFT2-7) Self-Passivated Copper Gates for Thin Film Silicon Transistors (Late-News)  
H. Sirringhaus, A. Kahn and S. Wagner, *Princeton Univ., U.S.A.* ..... 391

## Poster Presentation (15:30–17:30)

### LCp1: LC Materials-1

- (LCp1-1) Theory on the Successive Phase Transitions of Chiral Smectic Liquid Crystals  
T. Koda and H. Kimura\*, *Yamagata Univ., Japan and \*Fukui Univ. of Tech., Japan* ..... 53
- (LCp1-2) Computer Simulation on Liquid Crystal Order in Cell with Alignment Surface  
S. Kondo and I. Ono, *Science Univ. of Tokyo, Japan* ..... 57
- (LCp1-3) withdrawn
- (LCp1-4) Electrooptic Property of a Binary Mixture of Ferroelectric and Antiferroelectric Chiral Compounds Showing Thresholdless V-Shaped Switching  
S.S. Seomun, T. Gouda, T. Takanishi, K. Ishikawa, H. Takezoe, A. Fukuda, C. Tanaka\*, T. Fujiyama\*, T. Maruyama\* and S. Nishiyama\*, *Tokyo Inst. of Tech., Japan and \*Mitsui Petrochemical Industries, Japan* ..... 61
- (LCp1-5) Decrease in Voltage Holding Ratio of LCD Panels Due to Ionic and Organic Contaminants  
N. Sasaki and K. Shiotani, *NEC, Japan* ..... 65

### LCp2: LC Alignment Technologies-1

- (LCp2-1) Gray Shades Capability of SSFLCs by Using a Bookshelf Layer Structure FLC  
A. Mochizuki, T. Yoshihara and T. Makino, *Fujitsu Labs., Japan* ..... 69
- (LCp2-2) Evidence for SiO<sub>x</sub> Alignment Layer Modification by Ferro-Electric Liquid Crystal Flow-Surface Memory Effect on an Inorganic Alignment Layer  
G. Bodammer, A. O'hara, D.G. Vass and J. Crain, *Univ. of Edinburgh, U.K.* ..... 73
- (LCp2-3) Effects of the Ion Beam Irradiation on Liquid Crystal Aligning Properties of Rubbed Polymer Surfaces  
K. Hiroshima, A. Yamada, T. Ehara\*, H. Kuwahara\*\*, N. Asagi\*\*, M. Nakabayashi\*\*, S. Asakuma\*\*\*, T. Eguchi\*\*\*, H. Setoh\*\*\*\*, N. Okanami\*\*\*\* and M. Tsukiji\*\*\*\*\*, *Yamanashi Univ., Japan, \*E.H.C., Japan, \*\*Nissin Electric, Japan, \*\*\*Sumitomo Bakelite, Japan, \*\*\*\*Shintokogio, Japan and \*\*\*\*\*Uniopt, Japan* ..... 77

### TFTp1: poly-Si TFT Technologies & Modeling

- (TFTp1-1) Low Temperature Fabrication of TFT Using cat-CVD Si and Insulator Films  
A. Heya, H. Makino and H. Matsumura, *JAIST, Japan* ..... 81
- (TFTp1-2) Uniformity Improvement of Excimer Laser Crystallized poly-Si Thin Film Transistors  
K. Sera, H. Tanabe, H. Okumura, K. Yuda and F. Okumura, *NEC, Japan* ..... 85
- (TFTp1-3) Self-Heating of Polycrystalline Silicon Thin Film Transistors  
N. Takashima, M. Satoh, A. Tajima and T. Sameshima, *Tokyo A&T Univ., Japan* .... 89
- (TFTp1-4) Determination of the Interface State Density Generated by Hot-Carrier Effects in Polysilicon Thin Film Transistors  
R. Carluccio, L. Mariucci, A. Pecora, I. Policicchio and G. Fortunato, *IESS-CNR, Italy* ..... 93
- (TFTp1-5) Analysis and Modelling of the Leakage Current in Low-Temperature Polysilicon TFTs with a Thin Active Layer  
O.K.B.Lui, M.J.Quinn, S.W-B. Tam, P. Migliorato and H. Ohshima\*, *Univ. of Cambridge, U.K. and \*Seiko Epson, Japan* ..... 97

### TFTp2: TFT Process & Manufacturing-1

- (TFTp2-1) An Application of 40MHz Discharge for SiN<sub>x</sub> Film Deposition to a-Si:H TFT Fabrication  
K. Takechi, T. Takagi\*, S. Nishida and S. Kaneko, *NEC, Japan and \*ANELVA, Japan* ..... 101
- (TFTp2-2) Flexible Glass Substrates with Via Holes for TFT Backplanes  
H. Gleskova, E.Y. Ma, S. Wagner and D.S. Shen\*, *Princeton Univ., U.S.A., and \*Univ. of Alabama, U.S.A.* ..... 105

(TFTp2-3)	Data Line Metallizations of Cr and Mo C.W. Kim, M.K. Hur, C.O. Jeong, J.H. Kim, M.P. Hong, S.Y. Kim, H.R. Nam, J.H. Choi, H.G. Yang and J.H. Souk, <i>Samsung Electronics, Korea</i> . . . . .	109
(TFTp2-4)	Comparison of poly-Si Crystallinity by Laser Irradiation Methods and Their Applica- tion for poly-Si TFT's H. Tokioka, T. Sasagawa, T. Sakamoto and M. Inoue, <i>Mitsubishi Electric, Japan</i> . . .	113
(TFTp2-5)	A Novel Thin-Film Transistors with $\mu\text{c-Si/a-Si}$ Dual Active Layer Structure for AM-LCD Z. Xu, S. Zhang, C. Wang, X. Zhou, Y. Dai and B. Zhao, <i>Huazhong Univ. of Science &amp; Tech., China</i> . . . . .	117
(TFTp2-6)	Amorphous-Silicon Thin-Film Transistors with Hydrogen-Free $\text{SiO}_2$ Gate (Late-News) Y. Uchida, K. Taguchi, S. Takei and M. Matsumura*, <i>Teikyo Univ. of Sciencee &amp; Tech., Japan and *Tokyo Inst. of Tech., Japan</i> . . . . .	393
(TFTp2-7)	Highly Controlled and Localized Spacer Fabrication Technology for LCDs (Late-News) Z. Yaniv and S. Rotter*, <i>SI Diamond Tech., U.S.A. and *Soreq NRC, Israel</i> . . . . .	395

### LCDp1: LCD Modes & Related Topics

(LCDp1-1)	Multiple Line Addressed STN LCDs Using Arbitrary STN Drivers F. Matsu, M. Hoshino, H. Oniwa and S. Yamamoto, <i>Seiko Instruments, Japan</i> . . . .	121
(LCDp1-2)	Study of Polymer Network Ferroelectric Liquid Crystal Device Electric-Optic and Anti- Shocking Property W. Zhao, R. Sun, Y. Tian*, J. Guo and X. Huang, <i>Changchun Inst. of Physics, China and *Jilin Univ., China</i> . . . . .	125
(LCDp1-3)	Cell Design of UV Light Modified Multi-Domain Technology for Large Size TFT/ LCDs S. Suzuki, H. Takano, K. Nakayama, Y. Momoi and A. Takenaka, <i>IBM Japan, Japan</i> . . . . .	129
(LCDp1-4)	Initialization of Optically Compensated Bend-Mode LCDs K. Sueoka, H. Nakamura* and Y. Taira, <i>IBM Research, Japan*, IBM Japan, Japan</i> . . . . .	133
(LCDp1-5)	Advanced Spatial Light Modulator by Using Polymer Cell-Wall Type Liquid Crystal Light Shutter T. Asada and M. Hori, <i>Kyoto Univ., Japan</i> . . . . .	137
(LCDp1-6)	Polymer Dispersed Liquid Crystal Films Obtained by Fast-Cooling Method (Late-News) Q. Wang, I. Tsunoda*, Y. Tian, R. Sun and X. Huang, <i>Changchun Inst. of Physics, China and *Science Univ. of Tokyo, Japan</i> . . . . .	397

### LCDp2: High Performance TFT-LCDs

(LCDp2-1)	A Wide Viewing Angle LCD Controlled by a Lateral Electric Field S. Tahata, A. Tsumura, T. Kawato, Y. Masutani, A. Tamatani and F. Matsukawa, <i>Mitsubishi Electric, Japan</i> . . . . .	141
(LCDp2-2)	A Wide-Viewing Angle TFT-LCD with a Bias Voltage Controlled Method and a Com- pensation Method of Shading K. Miyashita, S. Matsuoka, S. Hori, M. Uno, H. Maeda, Y. Takubo and E. Takeda, <i>Matsushita Electric Industrial, Japan</i> . . . . .	145
(LCDp2-3)	Super-High-Aperture-Ratio TFT-LCD Structure J.H. Kim, S.I. Park, W.K. Kim, H.Y. Lee, K.H. Ryu, J.Y. Park and H.S. Soh, <i>LG Electronics, Korea</i> . . . . .	149
(LCDp2-4)	withdrawn	
(LCDp2-5)	Fabrication of Black Matrix on TFT-Array with High Aperture Ratio J.H. Kim, K.N. Lim, Y.J. Oh, S.H. Lee, C.W. Han, Y.M. Ha and H.S. Soh, <i>LG Electronics, Korea</i> . . . . .	153
(LCDp2-6)	A 1.3-in. TFT-LCD for SVGA with 519K Dots Y. Hayashi, M. Iida, T. Iwanaga, H. Kaneko, S. Nishihara, H. Kitagawa and S. Koike, <i>Sony, Japan</i> . . . . .	157

- (LCDp2-7) A Miniature High Resolution FLC Display (Late-News)  
 I.D. Rankin, D.C. Burns\*, A. O'Hara, G. Bodammer, J.T.M. Stevenson,  
 I. Underwood, D.G. Vaas and M.R. Worboys\*\*, *Univ. of Edinburgh, U.K.*, \*Xilinx  
*Development, U.K. and \*\*GEC-Marconi Research Center, U.K.* ..... 399

**Nov. 28, Thursday**

**LC1: LC Materials (9:00-10:25)**

- 9:00 (LC1-1) Supramolecular Hydrogen-Bonded Liquid Crystals (Invited)  
 T. Kato, *Univ. of Tokyo, Japan* ..... 161
- 9:25 (LC1-2) Line Tension in a SmC Monolayer Droplet Phase  
 F.N. Braun, Y. Tabe and H. Yokoyama, *ETL, Japan* ..... 165
- 9:45 (LC1-3) Monodisperse Polymeric Particles with Liquid Crystalline Cores  
 R.R. Clikeman, M.C. Wills and R.E. Wargo, *Rohm & Haas Company, U.S.A.* .... 169
- 10:05 (LC1-4) Kinetic Control and Dielectric Analysis of Phase-Separated Structure Affecting Electro-  
 Optical Effect for (Polymer/Liquid Crystal) Composite Films  
 H. Kikuchi, H-K. Jeong and T. Kajiyama, *Kyushu Univ., Japan* ..... 173

**LCD1: STN & Wide Viewing-Angle TFT-LCDs (10:45-11:50)**

- 10:45 (LCD1-1) Multiple Line Addressed LCDs-A Review (Invited)  
 H. Araki, T. Kuwata\*, Y. Hirai\*, M. Kitamura\* and H. Koh\*, *Optrex, Japan and  
 \*Asahi Glass, Japan* ..... 177
- (LCD1-2) withdrawn
- 11:10 (LCD1-3) Wide Viewing Angle OCB-Mode LCD Using Light Path Control  
 T. Miyashita and T. Uchida, *Tohoku Univ., Japan* ..... 181
- 11:30 (LCD1-4) Wide Viewing Angle TFT-LCD Panel with 4-Domain CTN  
 H. Murai, M. Suzuki, T. Suzuki, T. Konno and S. Kaneko, *NEC, Japan* ..... 185

**LCD2: Wide Viewing-Angle TFT-LCDs (13:40-14:45)**

- 13:40 (LCD2-1) Optical Performance of a Novel Compensation Film for Wide-Viewing-Angle  
 TN-LCDs (Invited)  
 H. Mori, Y. Itoh, Y. Nishiura, T. Nakamura and Y. Shinagawa, *Fuji Photo Film,  
 Japan* ..... 189
- 14:05 (LCD2-2) Development of 'Super-V' TFT-LCDs  
 M. Hirata, N. Watanabe, T. Shimada, M. Okamoto, S. Mizushima, H. Take and  
 M. Hijikigawa, *Sharp, Japan* ..... 193
- 14:25 (LCD2-3) A 14.5-Inch-Diagonal XGA In-Plane-Switching Mode LCD Addressed by Metal-  
 Source/Drain Top-Gate a-Si TFT  
 M. Fukumoto, M. Miyai, Y. Tateishi, M. Shibazaki, T. Inada, T. Yukawa,  
 M. Moriya, S. Matsumoto and Y. Ugai, *Hosiden, Japan* ..... 197

**LCD3: TFT-LCD Technologies (15:00-16:20)**

- 15:00 (LCD3-1) A High Aperture Ratio 11.3 inch-diagonal SVGA TFT-LCDs Fabricated by Reduced  
 Process Method  
 M. Shinjou, H. Nakamura, Y. Hatta, T. Nakagawa, T. Yukawa and Y. Ugai,  
*Hosiden, Japan* ..... 201
- 15:20 (LCD3-2) A 1.43-in 768K Dots TFT LCD for a Single Panel Rear Projection TV with Buried  
 Micro Lens Array  
 K. Kaise, H. Ichikawa, T. Fukuda, H. Kitai, F. Abe, S. Shima, N. Furuto,  
 H. Komatsu, Y. Tsubota, Y. Saito and H. Yamanaka, *Sony, Japan* ..... 205
- 15:40 (LCD3-3) Evaluating Effects of Pixel Electrical Characteristics on AMLCD Panels  
 D. Divekar, R. Raghuram, G. Shet and N. Matsui, *Applied Simulation Tech.,  
 U.S.A.* ..... 209
- 16:00 (LCD3-4) Scaling Theory of TFT/LCD  
 T. Tsukada, *Hitachi, Japan* ..... 213

## Poster Presentation (15:30–17:30)

### LCp3: LC Materials-2

- (LCp3-1) Study on Polymer Stabilization Using Liquid Crystalline Monomers  
H. Hasebe, K. Takeuchi and H. Takatsu, *Dainippon Ink & Chemicals, Japan* ..... 217
- (LCp3-2) Synthesis of Antiferroelectric Liquid Crystals Having a 2-Pentylcyclopentyl or 1,2-Dimethylheptyl Ester Group  
T. Kusumoto, K. Ogino, T. Hiyama\*, T. Isozaki\*\*, I. Kobayashi\*\* and Y. Suzuki\*\*, *Sagami Chemical Research Center, Japan, \*Tokyo Inst. of Tech., Japan and \*\*Showa Shell Sekiyu, Japan* ..... 221
- (LCp3-3) 2,4-Disubstituted- $\gamma$ -Butyrolactones for FLCs. Ferroelectric Properties Effected by Alkyl Length between Chiral Carbon and Core Part  
K. Sakaguchi, Y. Kawamura, Y. Ohfuné and S. Saito\*, *Osaka City Univ., Japan and \*Chisso Petrochemical, Japan* ..... 225
- (LCp3-4) Synthesis and Properties of Ferroelectric Liquid Crystals with Fluorinated Asymmetric Frames  
Y. Nagashima, Y. Aoki and H. Nohira, *Saitama Univ., Japan*..... 229
- (LCp3-5) Synthesis and Mesomorphic Properties of Some Tolane-Based Liquid Crystals with Tetrafluorophenylene Moiety  
H. Yin and J. Wen, *Chinese Academy of Sciences, China* ..... 233
- (LCp3-6) Magnetic Properties of Mixtures of Mesomorphic Copper (II) and Oxovanadium (IV) Complexes of 5,10,15,20-Tetrakis (4-*n*-dodecylphenyl) Porphyrin (Late-News)  
S. Tantrawong, M. Yoshida, T. Sugino and Y. Shimizu, *Osaka National Research Inst., Japan* ..... 401

### LCp4: LC Cell Accessment

- (LCp4-1) Residual DC Voltage Measurement Utilizing Capacitor's Dielectric Absorption Method  
N. Manabe, M. Inoue and J. Nakanowatari\*, *Toyo, Japan and \*Merck Japan, Japan*..... 237
- (LCp4-2) Determining Cell Gap and Twisted Angle of a Twisted Nematic Cell by Measuring Stokes Parameters  
Y. Zhou, Z. He and S. Sato, *Akita Univ., Japan* ..... 241

### LCp5: LC Alignment Technologies-2

- (LCp5-1) Optical Alignment of Nematic Liquid Crystal on Polyvinyl Cinnamate (PVC) Photopolymer and Anchoring Direction  
K. Rajesh, S. Masuda, R. Yamaguchi and S. Sato, *Akita Univ., Japan* ..... 245
- (LCp5-2) Relation among the Micro-Structure of Rubbing Fiber, Shape of the Microgroove of Polymer and Its Anchoring Strength -Correlation with the Ratio of the Total Area of Each Microgroove-  
K. Wako, K-Y. Han and T. Uchida, *Tohoku Univ., Japan*..... 249
- (LCp5-3) Pretilt Angle Reduction of an LC Cell by UV Exposure of the PI Alignment Film  
F. Yamada and Y. Taira, *IBM Research, Japan*..... 253
- (LCp5-4) Characterization of Rubbed Polyimide Film for LCDs with Reflection Ellipsometry  
I. Hirosawa and N. Hasegawa, *NEC, Japan* ..... 257
- (LCp5-5) A Study on the Anisotropy of Photo-Alignment Layer and the Order Parameter of Liquid Crystal (Late-News)  
K.Y. Han, B.H. Chae, S.H. Yu, J.G. Park\*, D.Y. Kim\*, S.T. Shin\*\* and Y.K. Joo\*\*, *Samsung Display Devices, Korea, \*Samsung Advanced Inst. of Tech., Korea and \*\*Samsung Electronics, Korea* ..... 403

### TFTp3: Evaluation & Analysis for a-Si TFTs

- (TFTp3-1) Analysis of Dynamic Characteristics of a-Si TFT  
J. Wang, S. Xiong, Y. Zhao, Q. Yuan and Y. Huang, *Nankai Univ., China* ..... 261

(TFTp3-2)	a-Si:H TFT-LCD Lifetime Evaluation with Gate-Line Delay Consideration C-S. Chiang, J. Kanicki, S. Nishida* and K. Takechi*, <i>Univ. of Michigan, U.S.A. and *NEC, Japan</i> .....	265
(TFTp3-3)	Power-Density-Dependent Failure of Amorphous-Si TFT M. Tada, S. Uchikoga and M. Ikeda, <i>Toshiba, Japan</i> .....	269
(TFTp3-4)	Bias-Stress Effect on the Performance of a-Si:H(:Cl) TFT S.K. Kim, K.S. Lee, J.H. Choi, C.S. Kim and J. Jang, <i>Kyung Hee Univ., Korea</i> ...	273
(TFTp3-5)	Effect of Transient Behavior of a-Si:H/Si <sub>3</sub> N <sub>4</sub> MIS Capacitors on Performance of a-Si:H Based TFT-LCDs M. Ishii, G. Kawachi and N. Konishi, <i>Hitachi, Japan</i> .....	277

#### **TFTp4: TFT Process & Manufacturing-2**

(TFTp4-1)	Edge Coverage Characteristics of Sputtered ITO Thin Films for TFT-LCDs M. Takabatake, E. Nishimura, K. Onisawa and T. Seino, <i>Hitachi, Japan</i> .....	281
(TFTp4-2)	An Analytical Study on Failure Mechanism Due to Glass Defects T. Sakai, H. Kuntzel, K. van Kampen, G. Roothans and D. Vandenhoudt, <i>Flat Panel Display, Netherlands</i> .....	285
(TFTp4-3)	Research on the Defects in Fine Pattern Processing and Redundant Technology C. Wu, Y. Zhao, Z. Zhou, J. Zhang, L. Yao, Y. Dai, S. Xiong and Z. Sun, <i>Nankai Univ., China</i> .....	289
(TFTp4-4)	An Appreciation Method for Sodium Ion Barrier Layer of SiO <sub>2</sub> of Glass Substrate Used in an Liquid Crystal Display R. Liu and S. Cheng, <i>Tianma Microelectronics, China</i> .....	293
(TFTp4-5)	Development of 2-Mask Fabrication Process of poly-Si TFT for University Education Y-H. Choi, J-H. Park* and C-J. Kim, <i>Seoul City Univ., Korea and *LG Electronics, Korea</i> .....	297
(TFTp4-6)	Flat Panel Display Test Head Based on Compliant Bump Technology (Late-News) N. Potter, N. Kumar and Z. Yaniv, <i>SI Diamond Tech., U.S.A.</i> .....	405

#### **LCDp3: LCD Modeling & Driving**

(LCDp3-1)	Complete Analysis of Various State of the Art AMLCD Structures with LIQUID P.G. Scrobhaci, J.G. Rollins and D. Durbeck, <i>Tech. Modeling Associates, U.S.A.</i> ....	301
(LCDp3-2)	10 $\mu$ A Quiescent Current Op-amp. Design for an LCD Driver IC T. Itakura and H. Minamizaki, <i>Toshiba, Japan</i> .....	305
(LCDp3-3)	Driving Method for Wide-Screen TFT-LCD K. Mizukata, Y. Nakahara, M. Tanaka, T. Iemoto and H. Yakushigawa, <i>Sharp, Japan</i> .....	309
(LCDp3-4)	Common Alternative Multi-Field Driving Method for Low Power TFT-LCDs H. Okumura, G. Itoh, K. Suzuki and K. Suzuki, <i>Toshiba, Japan</i> .....	313
(LCDp3-5)	Simulation of Horizontal Crosstalk in Point-at-Time Scheme with Matrix Parametric Model M. Kimura, T. Ozawa and H. Ohshima, <i>Seiko Epson, Japan</i> .....	317

### **Nov. 29, Friday**

#### **LCD4: Reflective LCDs (9:00-10:25)**

9:00	(LCD4-1) Recent Advances in Bistable Reflective Cholesteric Displays: Relaxation from Homeotropic Texture in Pulsed Cells (Invited) J.L. West, G.R. Magyar and H. Yoshida*, <i>Kent State Univ., U.S.A. and *Fujitsu, Japan</i> .....	321
9:25	(LCD4-2) Optimization Method for Black and White Representation in Reflective STN-LCDs with Single Polarizers S. Komura, O. Itoh and K. Kondo, <i>Hitachi, Japan</i> .....	325
9:45	(LCD4-3) A Single-Polarizer Reflective TFT-LCD E. Sakai, H. Nakamura, K. Yoshida and Y. Ugai, <i>Hosiden, Japan</i> .....	329



10:05	(LCD4-4)	Optical and Color Design of the Reflective Three-Layer Guest-Host Color LCD K. Taira, H. Iwanaga, A. Hotta, Y. Nakai, T. Ohtake and K. Sunohara, <i>Toshiba, Japan</i> .....	333
-------	----------	---------------------------------------------------------------------------------------------------------------------------------------------------------------------------------	-----

**LC2: LC Alignment Technologies (10:40–12:20)**

10:40	(LC2-1)	Optically Structured Multidomain LCDs with Broad Field of View and Gap Ferroelectric LCDs with Large Cell (Invited) M. Schadt, H. Seiberle and J. Funfschilling, <i>ROLIC, Switzerland</i> .....	337
11:05	(LC2-2)	Optically-Controlled Alignment of Nematic Liquid Crystals on Photo-Sensitive Polyimide Films H. Endo, T. Shinozaki*, H. Fukuro, Y. Iimura* and S. Kobayashi**, <i>Nissan Chemical Industries, Japan, *Tokyo A&amp;T Univ., Japan, **Science Univ. of Tokyo in Yamaguchi, Japan</i> .....	341
11:25	(LC2-3)	Correlation between Molecular Orientation of Side Chain of Alignment Layer and Liquid Crystal Monolayer Studied by Surface-Second-Harmonic Generation H. Takezoe, T. Sakai, Y. Kinoshita, T. Yamada, H. Hoshi, K. Ishikawa and A. Fukuda, <i>Tokyo Inst. of Tech., Japan</i> .....	345
11:45	(LC2-4)	An Effect of Alignment Layer on Polarization Switching of SSFLCs T. Yoshihara, Y. Kiyota, T. Makino, H. Shiroto and A. Mochizuki, <i>Fujitsu Labs., Japan</i> .....	349
12:05	(LC2-5)	Photo-Alignment of LC by Dye Containing Azo-Group (Late-News) J.K. Song, K.Y. Han and V.G. Chigrinov*, <i>Samsung Display Devices, Korea and *Niopik Organic Intermediates &amp; Inst., Russia</i> .....	407

**TFT3: Manufacturing, Process & Evaluation (13:30–14:55)**

13:30	(TFT3-1)	A High Throughput Ion Implanter for AMLCD's (Invited) M. Sato, J. Blake*, A. Brailove*, K. Chen*, M. King* and P.H. Rose*, <i>Sumitomo Eaton Nova, Japan and *Eaton, U.S.A.</i> .....	353
13:55	(TFT3-2)	One-Mask Ion Doping Technology for CMOS Structures of poly-Si TFTs A. Mimura, M. Nagai, Y. Shinagawa, G. Kawachi, Y. Mikami and T. Minemura, <i>Hitachi, Japan</i> .....	357
14:15	(TFT3-3)	Ellipsometry as Measurement of poly-Si Characteristics in Excimer Laser Annealed a-Si Thin Films I-C. Hsieh, C-H. Kuo*, T.W. Sigmon**, D.K. Schroder*, Y-H. Zhang*, S. Chen and G.N. Maracas***, <i>XMR, U.S.A, *Arizona State Univ., U.S.A., **Lawrence Livermore Lab., U.S.A. and ***Motorola, U.S.A.</i> .....	361
14:35	(TFT3-4)	Flexible, Lightweight Steel-Foil Substrates for Amorphous Silicon Thin-Film Transistors S.D. Theiss and S. Wagner, <i>Princeton Univ., U.S.A.</i> .....	365

**LCD5: Components & Application (15:10–17:10)**

15:10	(LCD5-1)	New Development of Large Size and High Resolution TFT-LCDs (Invited) H. Take, <i>Sharp, Japan</i> .....	369
15:35	(LCD5-2)	An Advanced COG(Chip On Glass) Technology for TFT-LCDs H. Takasago, T. Kokogawa*, O. Hayashi* and K. Adachi*, <i>Mitsubishi Electric, Japan and *Advanced Display, Japan</i> .....	373
15:55	(LCD5-3)	A New Low Power Consumption Fluorescent Lamp for LCD Backlighting K. Nishimura, K. Yuasa, Y. Hara and M. Takagi, <i>Toshiba Lighting &amp; Tech., Japan</i> ...	377
16:15	(LCD5-4)	A 6-Bit Digital Data Driver with 300/309 Outputs for Color TFT-LCDs N. Shimizu, T. Tazuke and K. Kitamura*, <i>NEC Kansai, Japan and *NEC, Japan</i> ...	381
16:35	(LCD5-5)	A New Head-Mounted Display Utilizing Multiple Polymer-Dispersed Liquid-Crystal Screens S. Suyama, K. Kato and S. Sakai, <i>NTT, Japan</i> .....	385
16:55	(LCD5-6)	Development of 512-Color-Reflective TFT-LCD (Late-News) Y. Itoh, N. Kimura, Y. Ishii, F. Funada and K. Awane, <i>Sharp, Japan</i> .....	409